

A M E N D M E N T DT09 Rec'd PCT/PTO 24 JUN 2004

To: Commissioner of the Patent Office, Mr. Yasuo Imai

1. Identification of the International Application  
PCT/JP02/13813

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4. Item to be Amended: Description and Claims

5. Content of Amendment

As shown in the separate sheets. More specifically,

(1) On page 2, lines 11 and 16, "page 482" is changed  
to --pages 482 - 484--.

(2) On page 3, line 17, "ultraviolet light" is changed  
to --ultraviolet light under certain conditions--.

(3) On page 3, lines 23 to 25, ", and in providing a  
photo-cleaning apparatus using the large-area quartz glass  
plate" is deleted.

(4) Page 3, lines 27 to 32 is changed as below:

"(1) A method for adhering a transparent material, comprising interposing an alkoxide between two materials, at least one of which comprises a medium transparent to ultraviolet light, externally applying a mechanical pressure to said two materials so as to reduce uneven gaps and improve contact between said two materials, using a nitrogen or rare earth gas atmosphere in order to prevent ultraviolet absorption, and irradiating ultraviolet light with a wavelength shorter than 200 nm to the above alkoxide portion, thereby adhering those two materials."

(5) Page 3, lines 33 to 37 is changed to as below:

"(2) An adhered quartz glass plate comprising two or more quartz glass plates laterally adhered in accordance with the adhering method as recited (1) above to provide a larger area, with the adhered part being transparent to ultraviolet light at a wavelength shorter than 350 nm."

(6) Page 4, lines 1 to 11 is changed as below:

"(3) A photo-cleaning apparatus comprising a light source part having one or a plurality of excimer lamp(s) or low-pressure mercury lamp(s), by which ultraviolet light is irradiated from said light source to an article to be cleaned disposed in a cleaning chamber, characterized in that the adhered quartz glass plate as recited (2) above is used for a window between the light source part and the cleaning chamber."

(7) On page 5, line 32, "The reason" is changed to --Although it is not intended to limit the present invention by the theory, the reason--.

(8) Page 6, lines 19 to 24 is changed as below:

"In the present invention, vacuum ultraviolet light at a wavelength shorter than 200 nm is suitably used."

(9) On page 6, lines 27 to 28, "having a wavelength in the vicinity of 254 nm and 185 nm" is deleted.

(10) On page 7, line 8, --(adhered materials)-- is added after "materials to be adhered".

(11) On page 7, line 17, "each other. The" is changed to --each other; the--.

(12) On page 7, line 23, "It is confirmed" is changed to --It is considered--.

(13) On page 8, line 12, "method" is changed to --above method--.

(14) On page 8, lines 12 and 17, "joining (adhering)" and "joined (adhered)" are changed to --adhering-- and --adhered-- respectively.

(15) On page 8, lines 31 to 32, "The adhering method of the present invention preferably has" is changed to --It is preferred to have--.

(16) On page 8, line 35, "In the adhesion process" is changed to --In the adhesion process of the present invention--.

(17) On page 9, line 2, "preferably" is deleted.

(18) On page 10, line 19, "2 mm" is changed to --2 cm--.

(19) Claim 1 is changed as below:

"1. A method for adhering a transparent material, comprising interposing an alkoxide between two materials, at least one of which comprises a medium transparent to ultraviolet light, externally applying a mechanical pressure to said two materials so as to reduce uneven gaps and improve contact between said two materials, using a nitrogen or rare earth gas atmosphere in order to prevent ultraviolet absorption, and irradiating ultraviolet light with a wavelength shorter than 200 nm to the above alkoxide portion, thereby adhering those two materials."

(20) Claim 2 is changed as below:

"2. An adhered quartz glass plate comprising two or more quartz glass plates laterally adhered in accordance with the adhering method as set forth in claim 1 to provide a larger area, with the adhered part being transparent to ultraviolet light at a wavelength shorter than 350 nm."

(21) Claim 3 is changed as below:

"3. A photo-cleaning apparatus comprising a light source part having one or a plurality of excimer lamp(s) or low-pressure mercury lamp(s), by which ultraviolet light is irradiated from said light source to an article to be cleaned disposed in a cleaning chamber, characterized in that the adhered quartz glass plate as set forth in claim 2 is used for a window between the light source part and the cleaning chamber."

6. List of Attached Sheets

Description, pages 2, 3, 3/1, 4, 5, 5/1, 6, 7, 7/1, 8, 9  
and 10 each one copy  
Claims (page 13) one copy